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TRANSLATION KEY: * English Abstract. ^f Concise statement of relevance provided in foreign search report. ^c Concise statement of relevance provided in specification or in attachment to document. ^s Concise statement of relevance provided in IDS. ^p Relevant portion of document translated. ^o English abstract only - copy of document in pct search.							
OTHER INFORMATION DISCLOSURE CITATIONS (Including Author, Title, Date, Pertinent Pages, Etc.)							
/J.S./	01	STEVENSON S. et al.; "Small-bandgap endohedral metallofullerenes in high yield and purity"; NATURE, September 2, 1999, Macmillan Magazines, UK, Vol. 401, No. 6748, Pages 55-57 XP002262357 ISSN: 0028-0836					
/J.S./	02	DATABASE CA "Online! Chemical Abstracts Service, Columbus, Ohio, US; FENG, Lai et al.; "Isolation and characterization of the endohedral metallofullerene Tb3N@C8"; Database accession no. 137:209802 CA XP002262359 Zusammenfassung & Gaodeng Xuexiao Huaxue (2002), 23(6), 996-998, 2002					
/J.S./	03	TAGMATARCHIS Nikos et al.; "Isolation and spectroscopic study of a series of mono and dierbium endohedral C82 and C84 metallofullerenes"; J Phys Chem B; Journal of Physical Chemistry B, November 2000, ACS, Washington, D.C., USA, Vol. 104, No. 47, Pages 11010-11012, XP002262358					
EXAMINER Jennifer A. Smith /Jennifer Smith/				DATE CONSIDERED 11/02/2008			
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